

a plurality of data lines arranged to cross the gate lines, for defining a pixel region on the array region; and

a light leakage prevention film formed between the gate lines and/or data lines of the array peripheral region, for preventing light leakage, the array peripheral region excluding pixel electrodes.

2. (Amended) The display panel as claimed in claim 1, further comprising:

a TFT and a pixel electrode formed in each pixel region located in the array region.

9. (Amended) A method for manufacturing a display panel including a first substrate having an array region and an array peripheral region, and a second substrate having a black matrix, the method comprising the steps of:

forming a plurality of gate lines on the first substrate;

forming a gate insulating film on the first substrate including the gate lines;

forming a plurality of data lines to cross the gate lines and define a pixel region on the array region; and

forming a light leakage prevention film between the gate lines and/or the data lines of the array peripheral region to prevent light leakage, the array peripheral region excluding pixel electrodes.

10. (Amended) The method according to claim 9, further comprising the steps of:

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forming a TFT at a crossing point of a corresponding one of the gate lines and a corresponding one of the data lines;

forming a passivation film on the first substrate including the TFT; and

forming, in the array region, a pixel electrode coupled with the TFT on the passivation film.

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